00862.022246

## **PATENT APPLICATION**

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
	: Examiner: H. Nguyen
Kazunori IWAMOTO et al.	)
	: Group Art Unit: 2851
Application No.: 09/866,600	)
Fil. 1. M 20. 2001	•
Filed: May 30, 2001	)
For: STAGE APPARATUS WHICH SUPPORTS	) April 30, 2003
INTERFEROMETER, STAGE POSITION	;
MEASUREMENT METHOD, PROJECTION	)
EXPOSURE APPARATUS, PROJECTION	
EXPOSURE APPARATUS MAINTENANCE	)
METHOD, SEMICONDUCTOR DEVICE	:
MANUFACTURING METHOD, AND	)
SEMICONDUCTOR MANUFACTURING FACTORY	:
The Commissioner for Patents	
Weshington D.C. 20221	

Washington, D.C. 20231

## <u>AMENDMENT</u>

Sir:

In response to the Official Action dated January 30, 2003, please amend the aboveidentified application as follows:

## INTRODUCTORY COMMENTS

This Amendment has been prepared in accordance with the Revised Format established by the U.S. Patent and Trademark Office, as permitted in the Pre-OG Notice dated February 4, 2003, and entitled "Amendments in a Revised Format Now Permitted."